



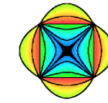
UNIVERSITÄT
LEIPZIG

Amorphous multi-cation and multi-anion oxide semiconductors: material design, carrier transport and device applications

Leipzig, 06.11.2020

Antonia Welk

Online Physikerinnentagung, Hamburg



- AG Grundmann
- Prof. Marius Grundmann
- Dr. Holger von Wenckstern
- Dr. Anna Reinhardt
- Dr. Peter Schlupp
- Dr. Daniel Splith
- Arne Jörns
- Oliver Herrfurth
- Oliver Lahr
- Michael Bar
- Jörg Lenzner



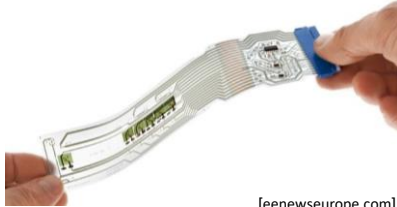
[IndiaTVnews.com]

APPLICATIONS OF AMORPHOUS OXIDE SEMICONDUCTORS

Wearable electronics



[wearable-technologies.com]



[eeneurope.com]

Smart windows



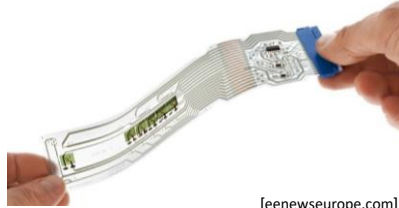
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APPLICATIONS OF AMORPHOUS OXIDE SEMICONDUCTORS

Display technology



[media4growth.com]



[Grzegorz Petrykowski/Shutterstock]



[www.teltarif.de]

THIN FILM TRANSISTOR MATERIALS

flexible



- amorphous
- magnetron sputtering
- room temperature deposition

THIN FILM TRANSISTOR MATERIALS

flexible



transparent



- amorphous
- magnetron sputtering
- room temperature deposition
- wide bandgap material

THIN FILM TRANSISTOR MATERIALS

flexible

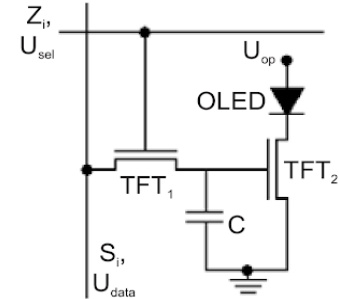


transparent



AMOLEDs

$$\vec{j} = en\mu\vec{E}$$

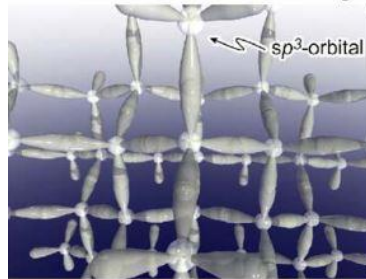


- amorphous
- magnetron sputtering
- room temperature deposition
- wide bandgap material
- high field effect mobilities $\mu > 20 \text{ cm}^2/\text{Vs}$ [1]

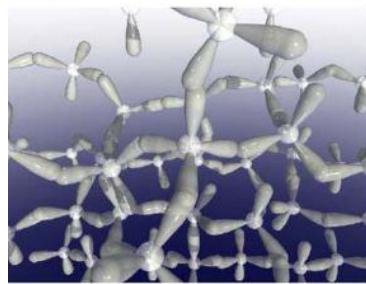
IONIC OXIDE SEMICONDUCTORS

covalent

crystalline

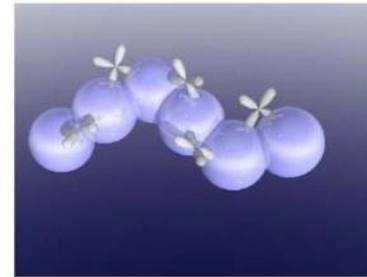
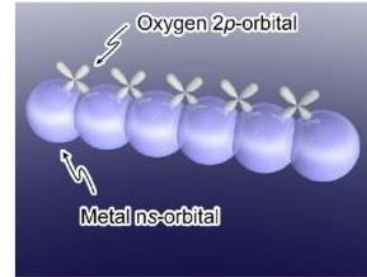


amorphous



ionic

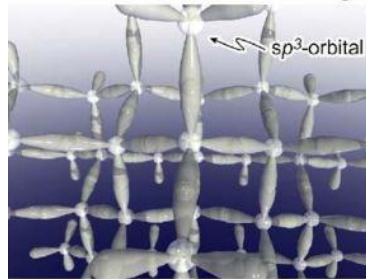
metal: $(n-1)d^{10}ns^0$ ($n \geq 5$)



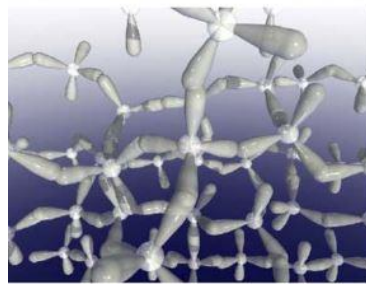
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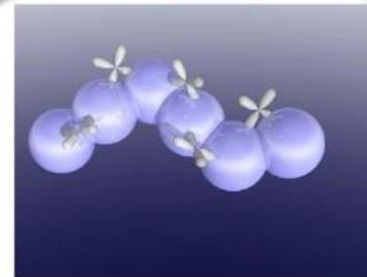
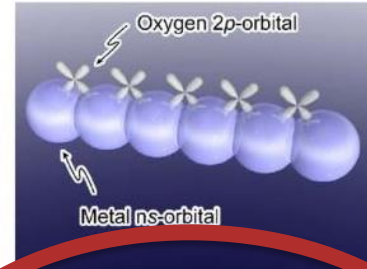
crystalline



amorphous



ionic
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POSSIBLE TRANSITION METALS

9 10 III IV V

29 Cu 63,54	30 Zn 63,54	31 Ga 63,54	32 Ge 63,54	33 As 63,54
47 Ag 63,54	48 Cd 63,54	49 In 63,54	50 Sn 63,54	51 Sb 63,54
79 Au 63,54	80 Hg 63,54	81 Tl 63,54	82 Pb 63,54	83 Bi 63,54

[Schlupp2018]

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[Schlupp2018]



critical raw materials

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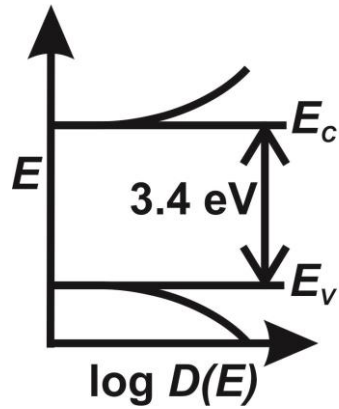
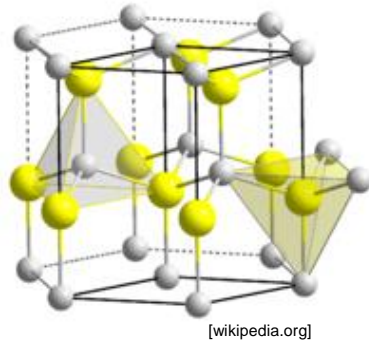
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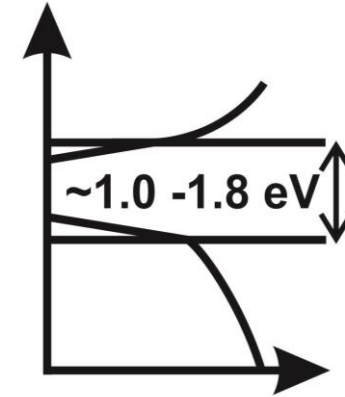
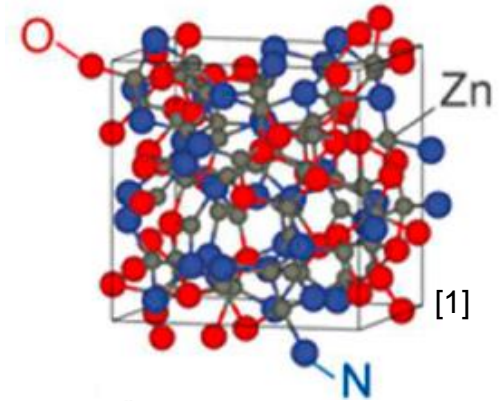


critical raw materials

ZINC OXIDE



ZINC OXYNITRIDE



AMORPHOUS OXIDE SEMICONDUCTORS

anionic disorder

- a-ZnON $\mu = 100 \text{ cm}^2/\text{Vs}$



cationic disorder

- a-InGaZnO $\mu = 20 \text{ cm}^2/\text{Vs}$
- a-ZnSnO $\mu = 13 \text{ cm}^2/\text{Vs}$



[Lahr2020]



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anionic disorder

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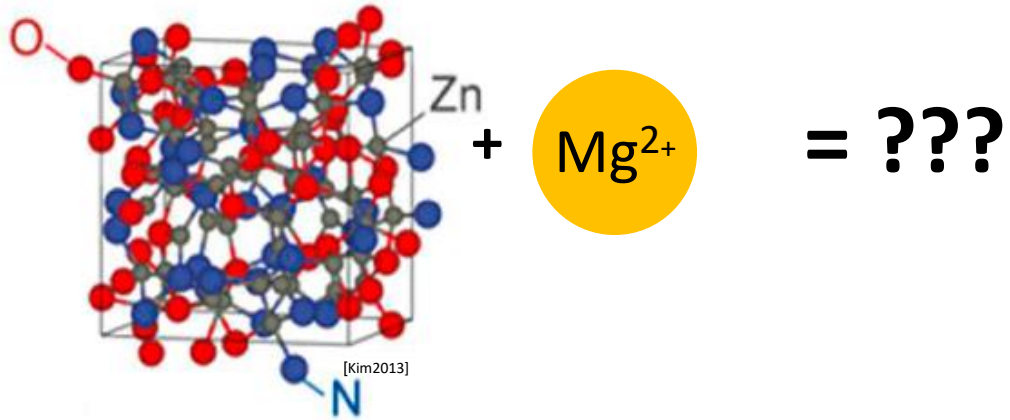
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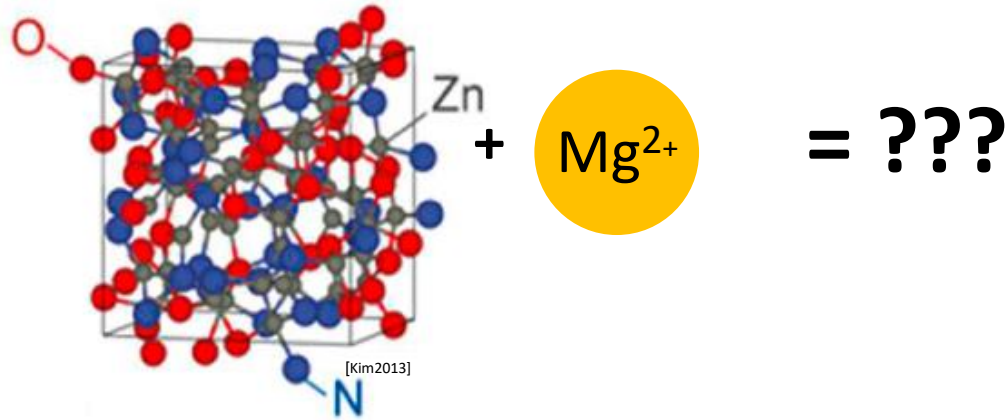


[Lahr2020]



Combining cationic and
anionic disorder ?





Goal: deposition of ZnMgON thin films

FROM MATERIAL DEPOSITION TO DEVICE FABRICATION

**Material design of
ZnMgON thin films**

FROM MATERIAL DEPOSITION TO DEVICE FABRICATION

Material design of
ZnMgON thin films

ZnMgON based **pn-**
heterodiodes

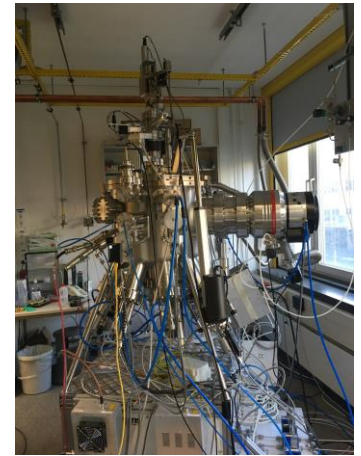
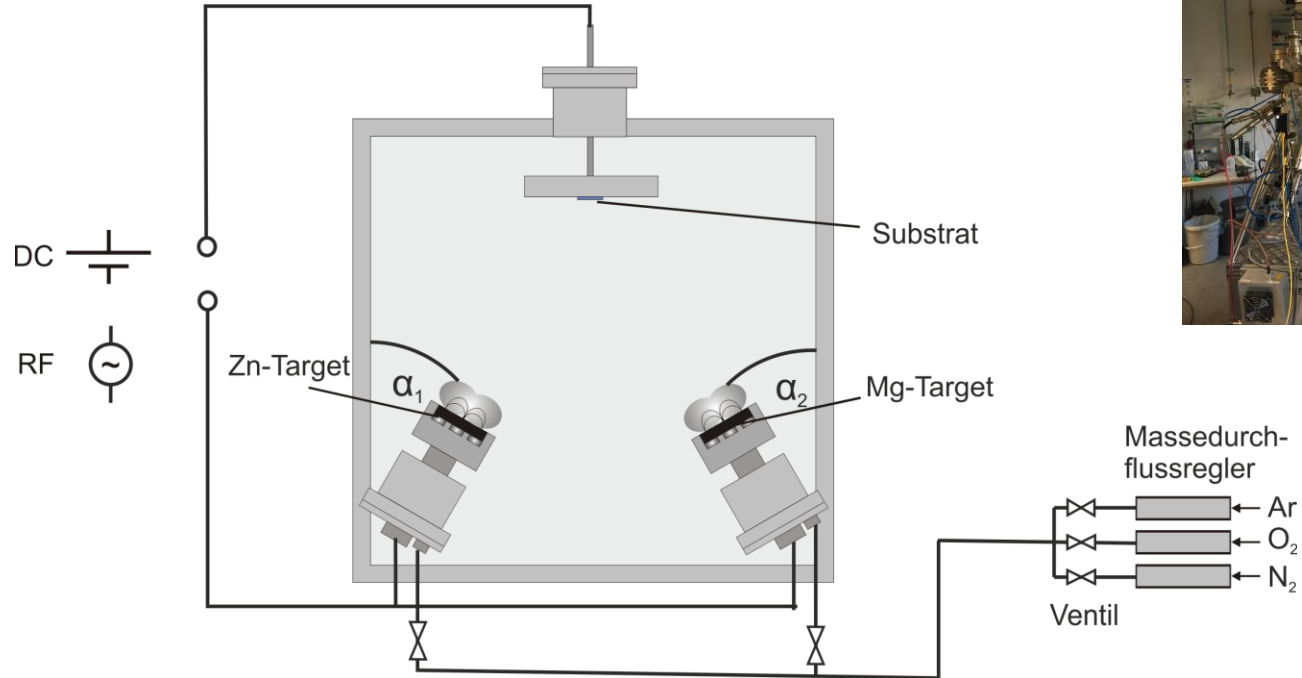
FROM MATERIAL DEPOSITION TO DEVICE FABRICATION

Material design of
ZnMgON thin films

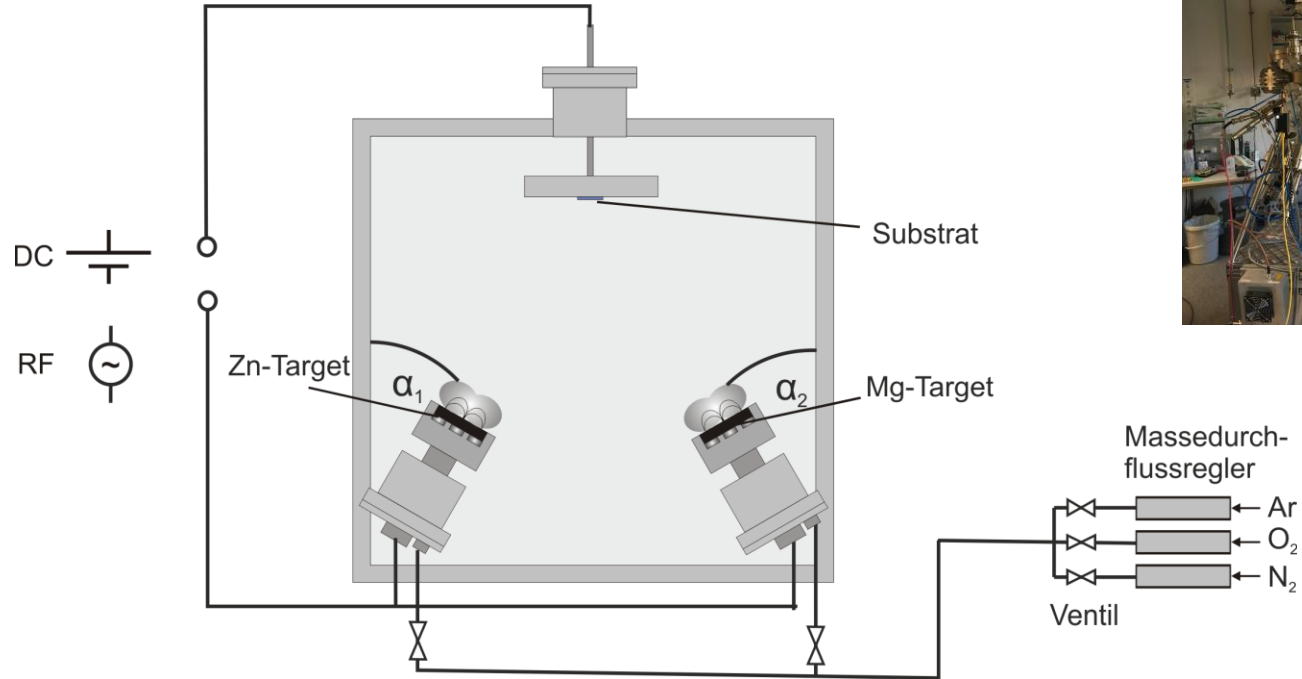
Percolation
description of
charge transport in
a-ZnON and a-ZTO

ZnMgON based **pn-**
heterodiodes

MAGNETRON CO-SPUTTERING

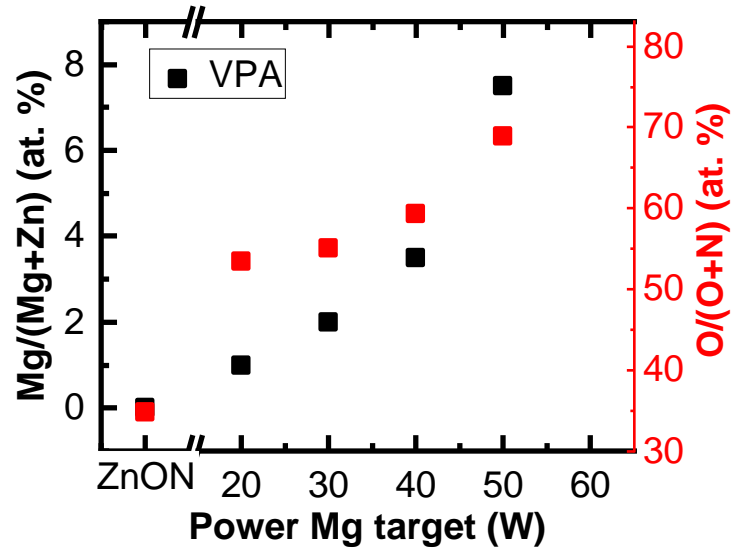


MAGNETRON CO-SPUTTERING



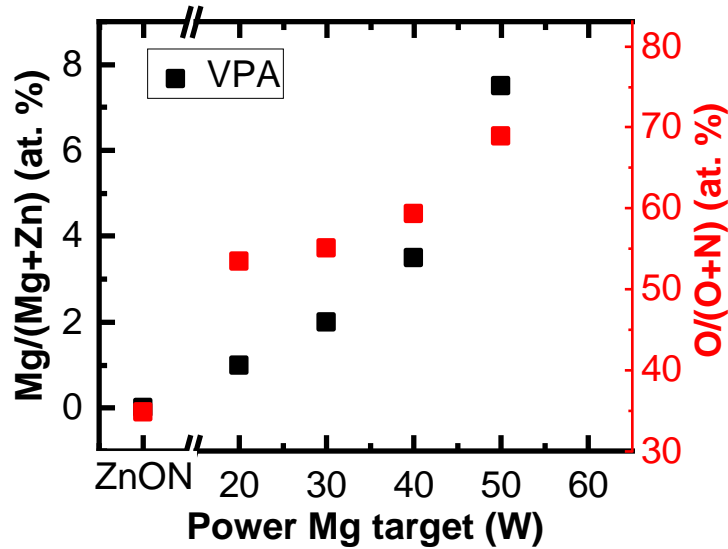
How to vary the chemical composition of the thin films?

CHEMICAL COMPOSITION

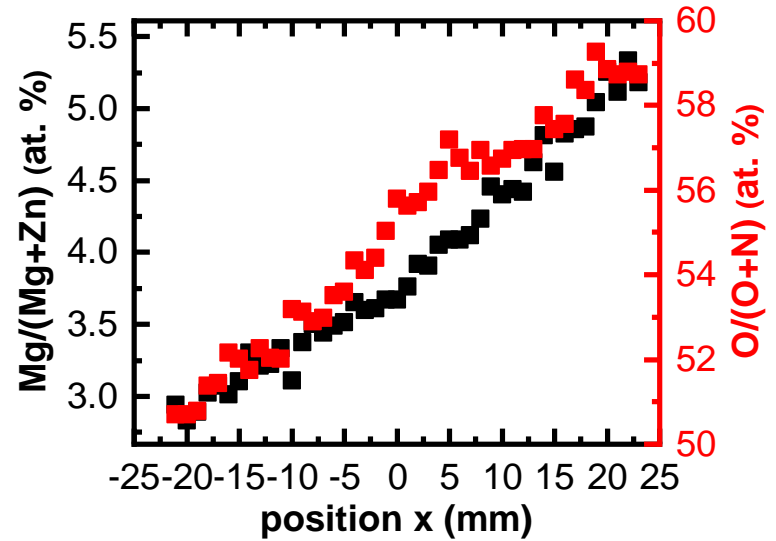


Variable power approach

CHEMICAL COMPOSITION

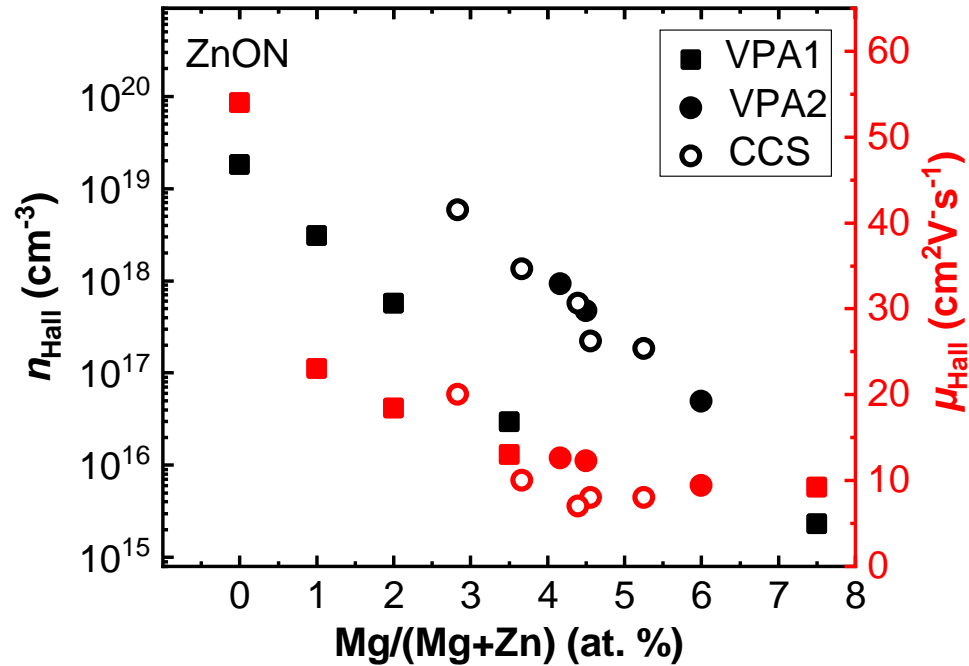


Variable power approach

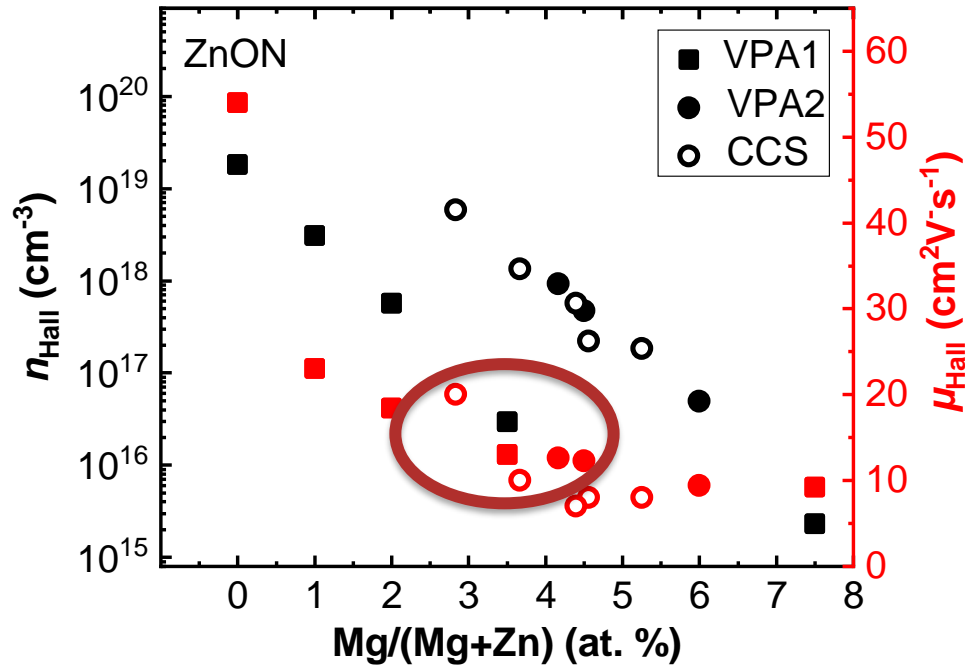


Continuous composition spread

ELECTRICAL PROPERTIES

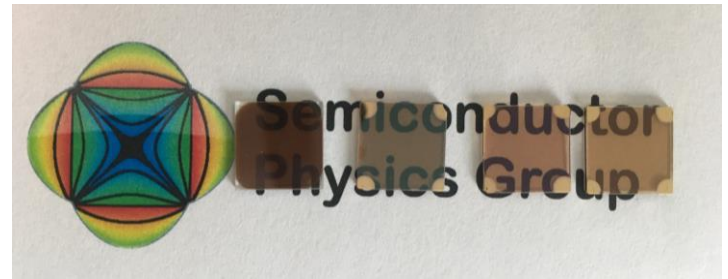


ELECTRICAL PROPERTIES

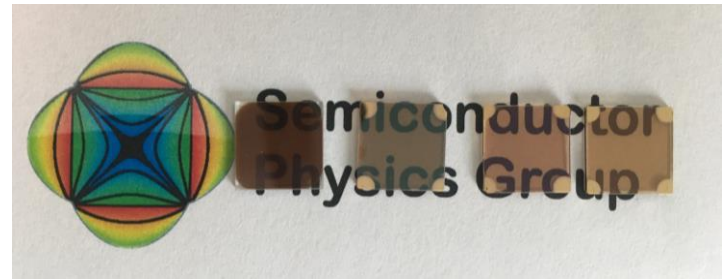
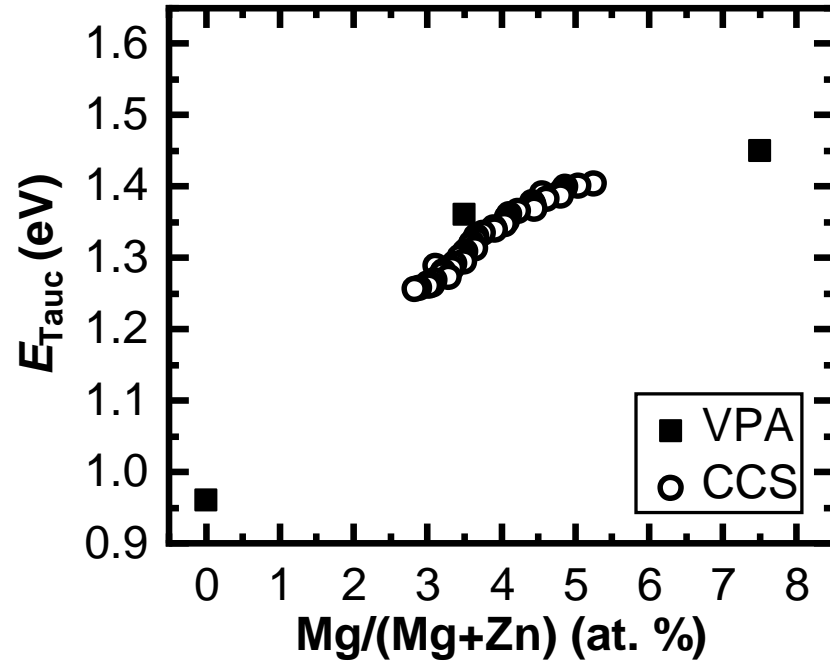


new electrical properties regime
 $n \sim 10^{17} \text{ cm}^{-3}$ and $\mu < 20 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$

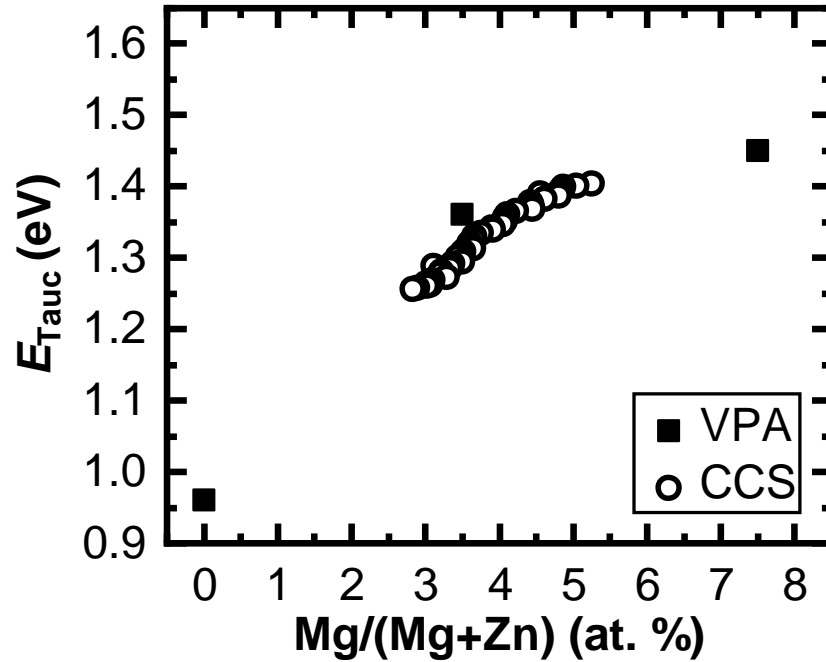
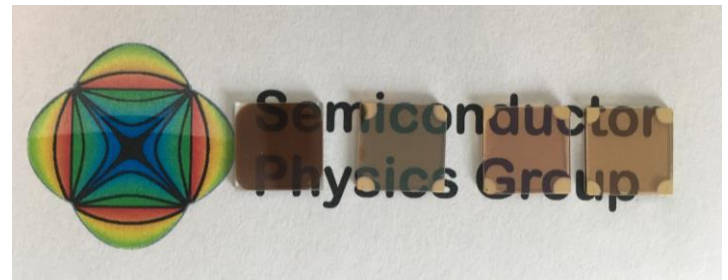
OPTICAL PROPERTIES



OPTICAL PROPERTIES



OPTICAL PROPERTIES



ZnMgON slightly more transparent than a-ZnON

FIGURE OF MERIT

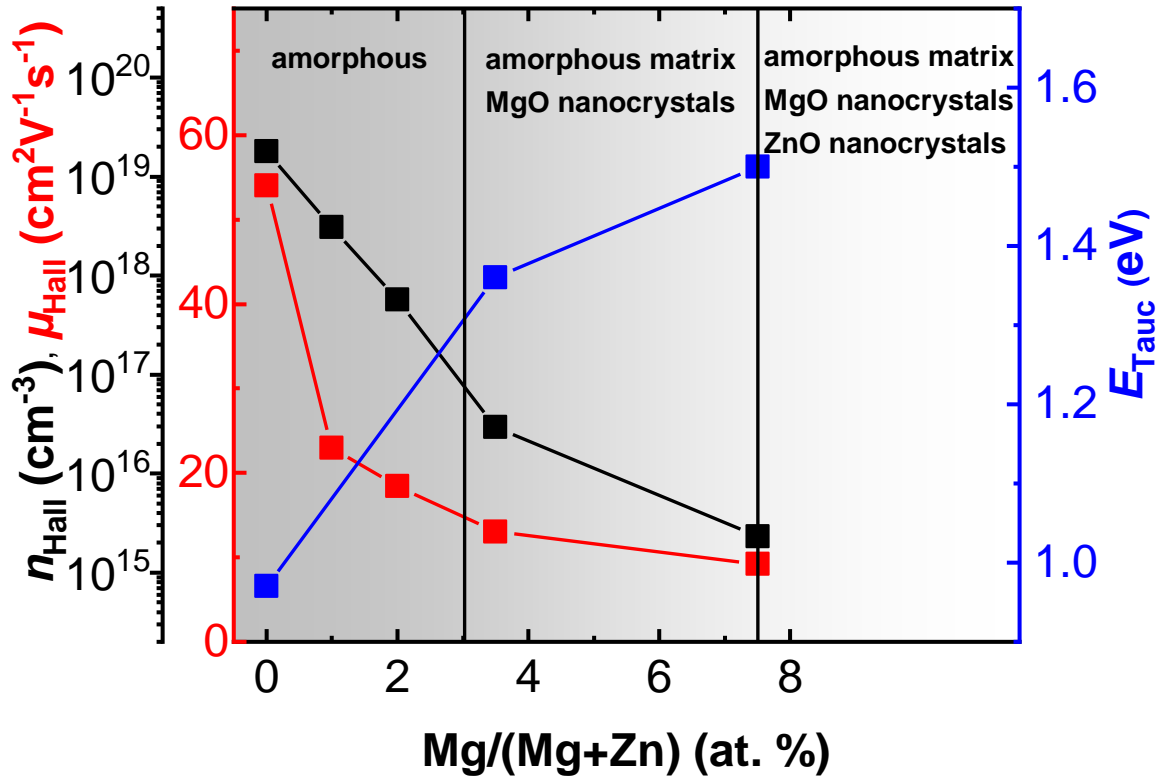
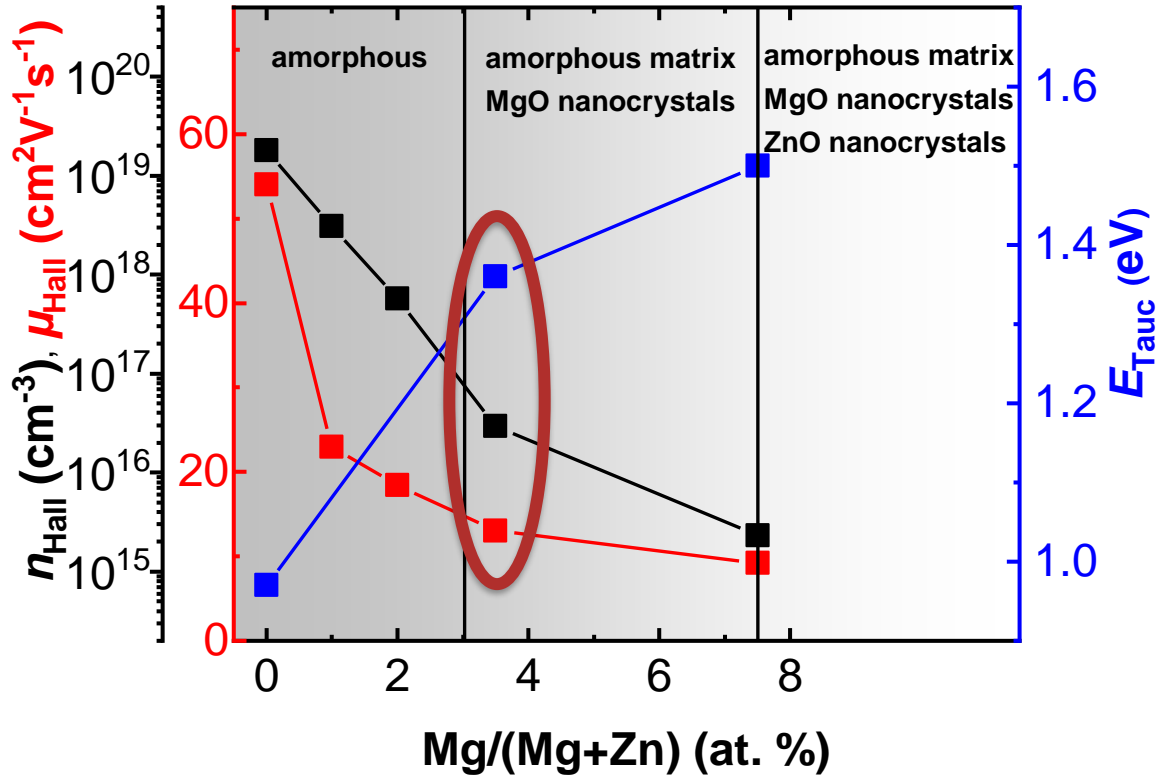
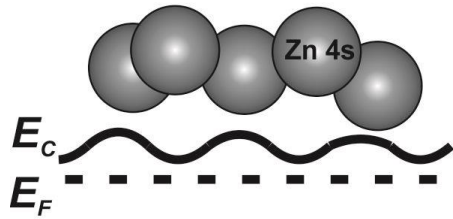


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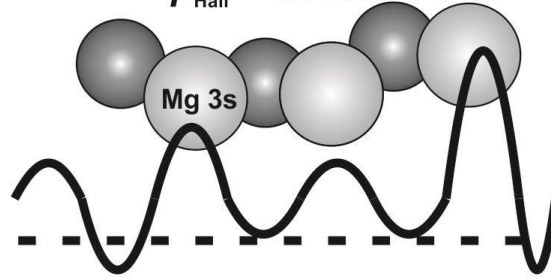
**Single cation
amorphous ZnON**

$$\mu_{\text{Hall}} = 50\text{-}100\text{cm}^2\text{V}^{-1}\text{s}^{-1}$$



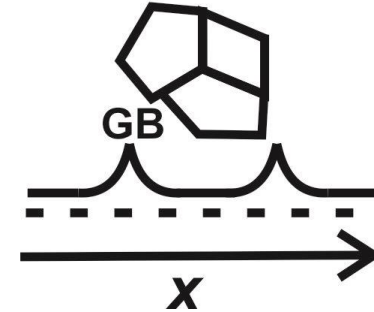
**Multi cation
amorphous ZnMgON**

$$\mu_{\text{Hall}} = 10\text{-}23\text{cm}^2\text{V}^{-1}\text{s}^{-1}$$



**MgO and ZnO
nanocrystals with GB**

$$\mu_{\text{Hall}} < 15\text{cm}^2\text{V}^{-1}\text{s}^{-1}$$



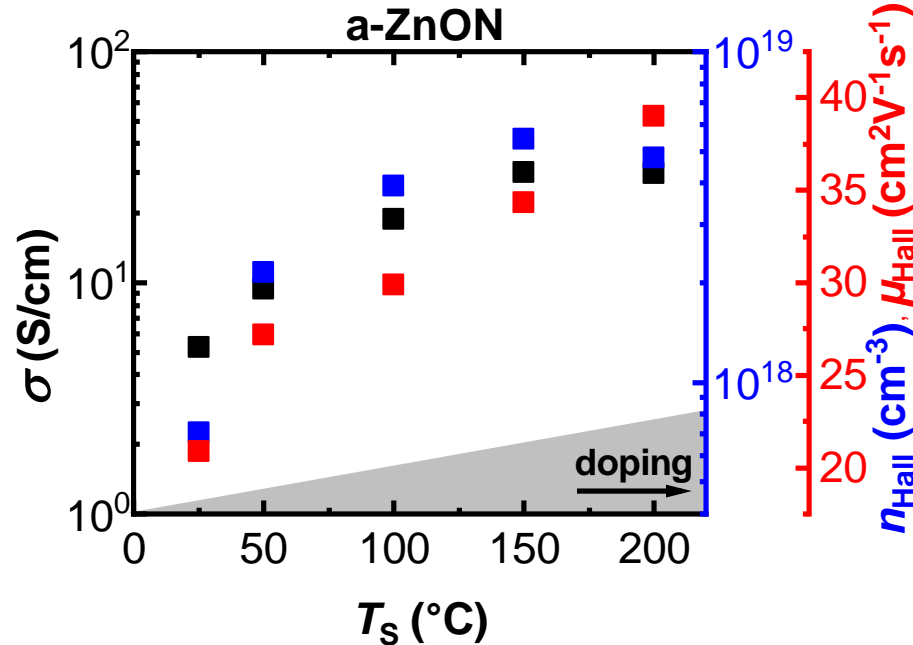
What is the effect of cationic substitution?

DESCRIPTION OF CHARGE TRANSPORT - COMBINATION OF THEORY AND EXPERIMENT

- 1) **Deposition** of thin films with varying doping
- 2) **Measuring** temperature dependent electrical properties
- 3) **Applying** a suitable **theoretical model**
- 4) **Extracting** parameters giving new material insights

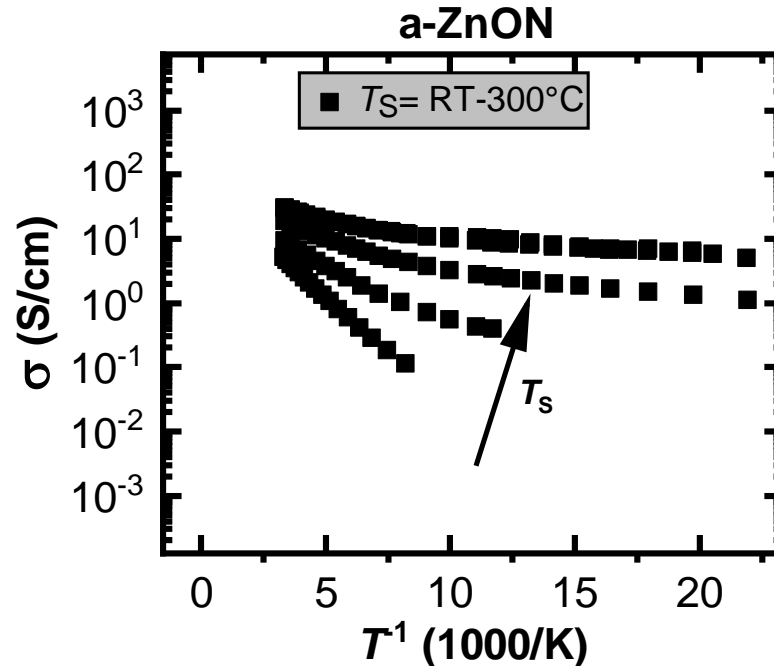
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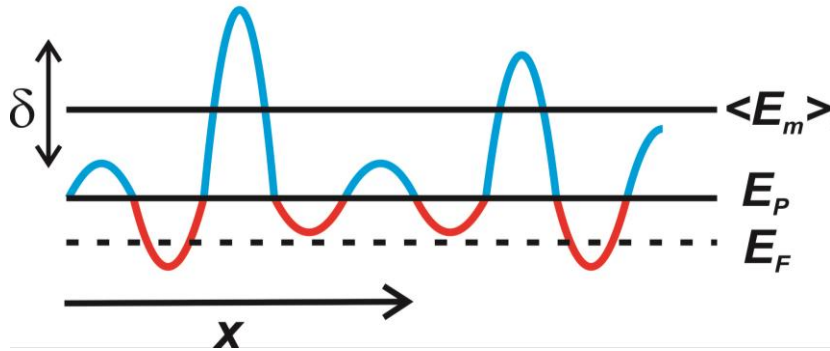
DESCRIPTION OF CHARGE TRANSPORT - COMBINATION OF THEORY AND EXPERIMENT

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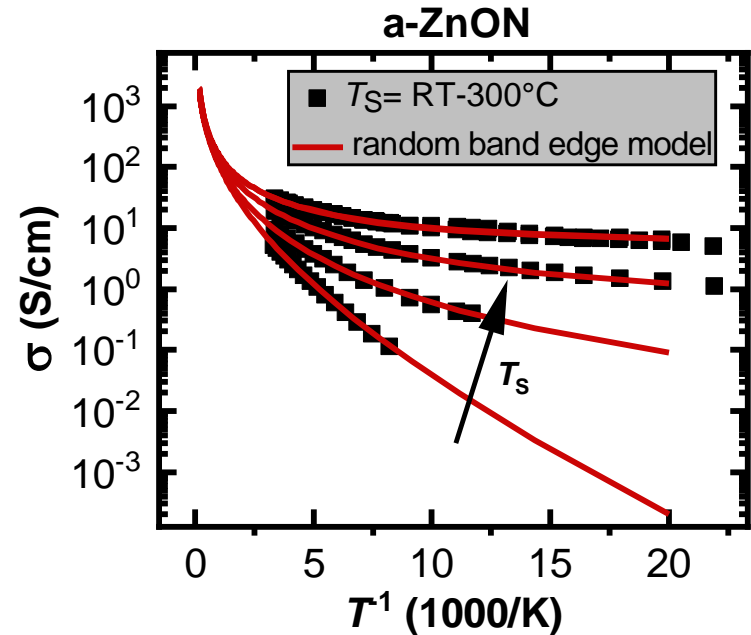
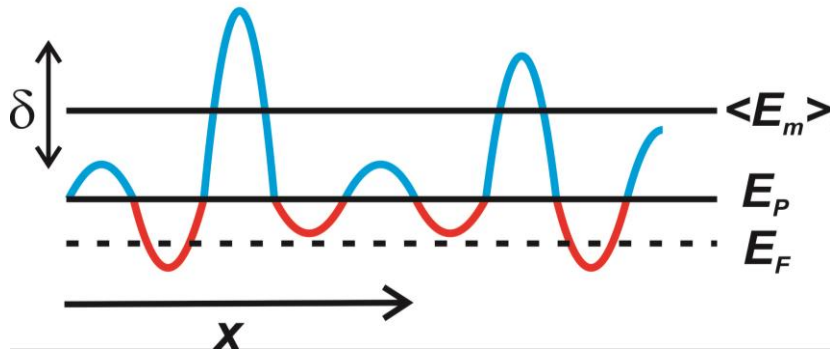
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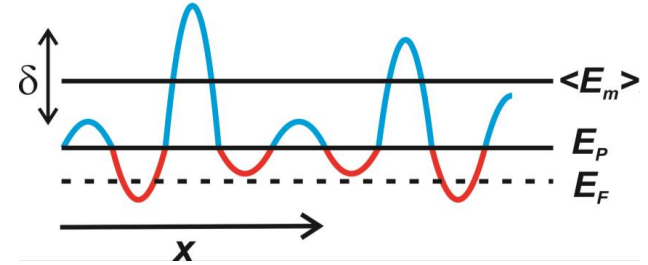
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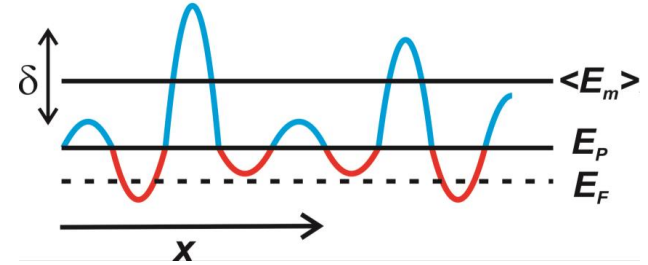
DESCRIPTION OF CHARGE CARRIER TRANSPORT - COMBINATION OF THEORY AND EXPERIMENT

4) **Extracting** parameters giving new material insights



DESCRIPTION OF CHARGE CARRIER TRANSPORT - COMBINATION OF THEORY AND EXPERIMENT

4) **Extracting** parameters giving new material insights



a-ZnON

$$\delta \sim 20 \text{ meV}$$

a-IGZO

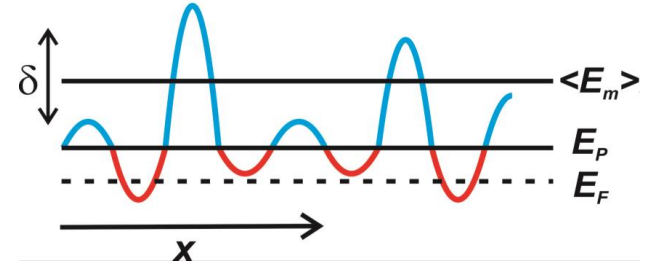
$$\bar{\delta} = 38.5 \text{ meV}$$

a-ZTO

$$\bar{\delta} = 60 \text{ meV}$$

DESCRIPTION OF CHARGE CARRIER TRANSPORT - COMBINATION OF THEORY AND EXPERIMENT

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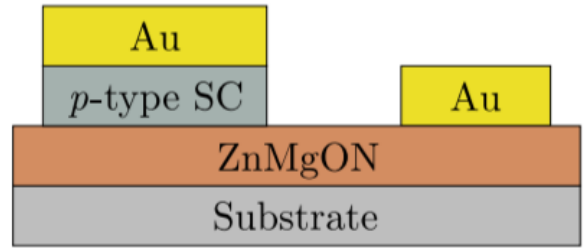
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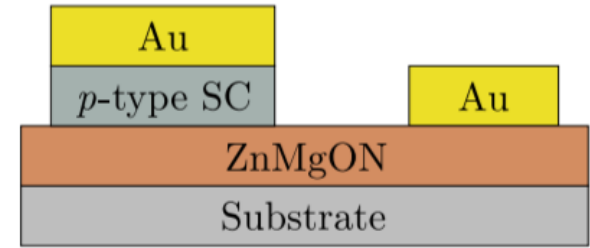
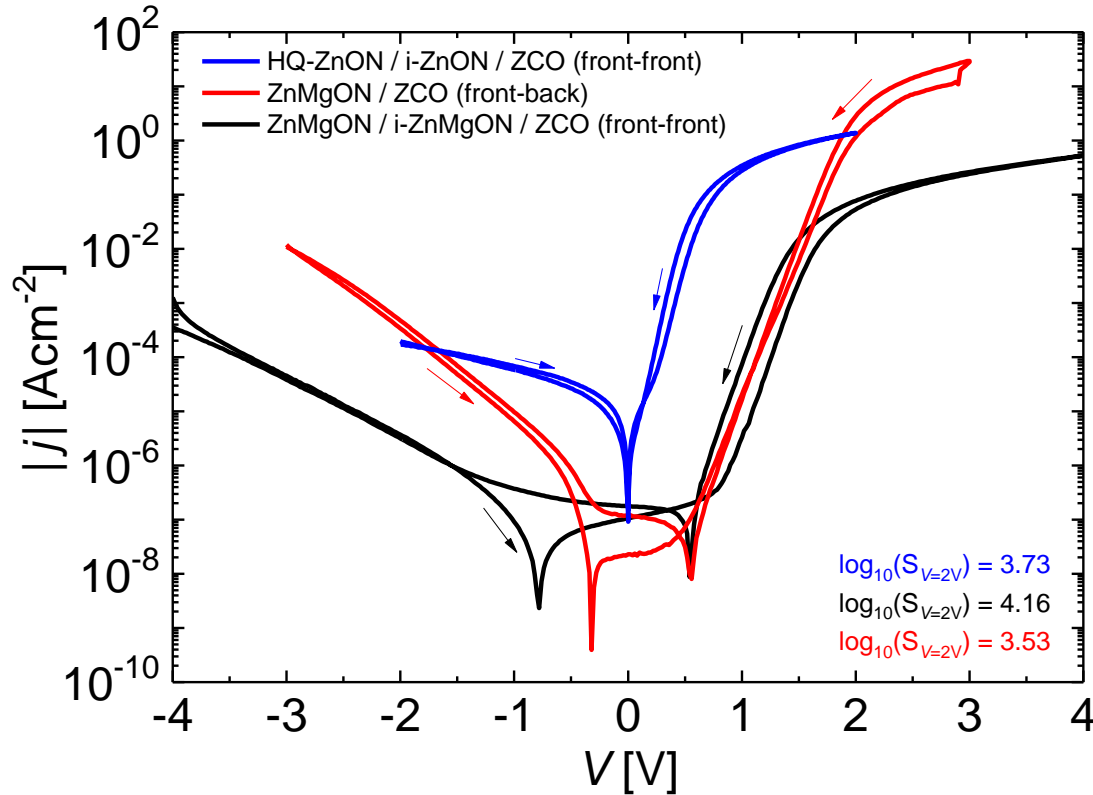
$$\bar{\delta} = 60 \text{ meV}$$

Multi-anion compound show less potential
fluctuations than multi-cation compounds

AMORPHOUS PN HETERODIODE



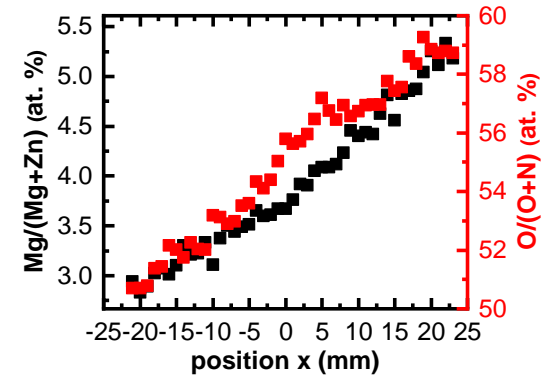
AMORPHOUS PN HETERODIODE



- n-type ZnMgON and p-type Zinc cobalt oxide (ZCO)
- high tunneling currents in backwards direction
- enhancement of rectification ratio

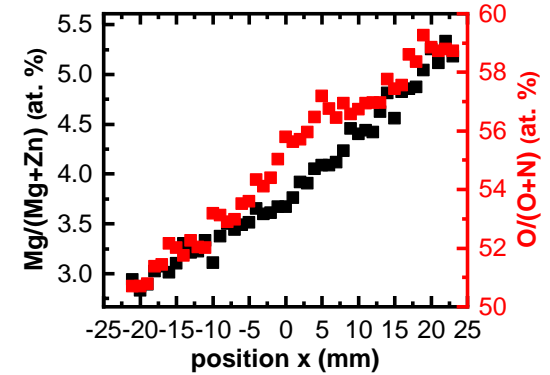
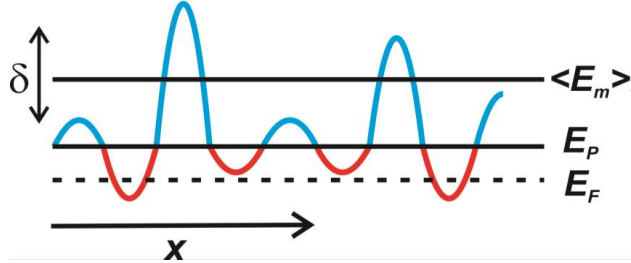
SUMMARY

- Deposition of a continuous composition spread
- Electrical properties of a-ZnON are tunable by magnesium cation substitution between $n=10^{19}\text{cm}^{-3}$ and $n=10^{15}\text{cm}^{-3}$



SUMMARY

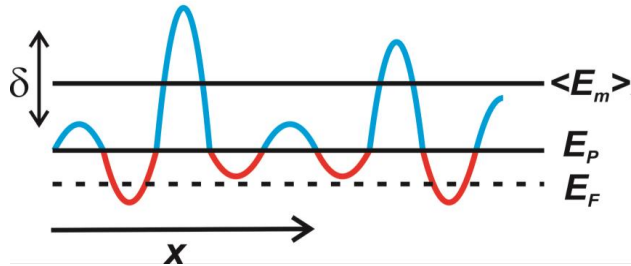
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- Percolation theory can be applied to determine the distribution of the conduction band edge

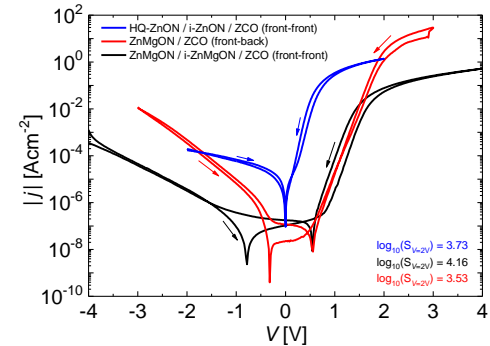
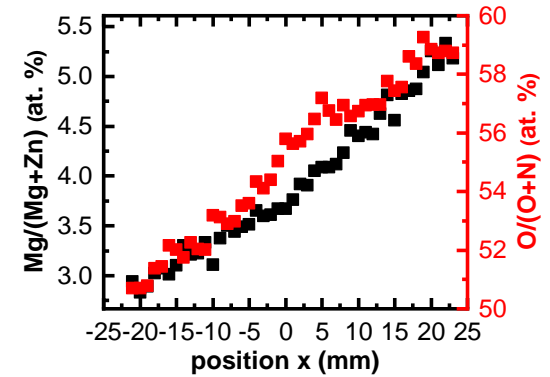
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- Percolation theory can be applied to determine the distribution of the conduction band edge

- Amorphous pn heterodiode n-ZnMgON/p-ZCO





UNIVERSITÄT
LEIPZIG



THANK YOU FOR YOUR ATTENTION!

Antonia Welk

Fakultät für Physik und Geowissenschaften

Linnéstraße 5, 04103 Leipzig

Tel +49 341 97-32615

antonia.welk@physik.uni-leipzig.de

www.uni-leipzig.de

BACKUP

THIN FILM TRANSISTOR MATERIALS

	a-Si:H	pc-Si	amorphous oxides
electron mobility	1 cm ² /Vs	30-100 cm ² /Vs	1-100 cm ² /Vs
process temperature	150-350°C	250-550°C	RT – 600°C
substrate	glass	glass	glass and plastic
uniformity	yes	no	yes
cost	low	high	low

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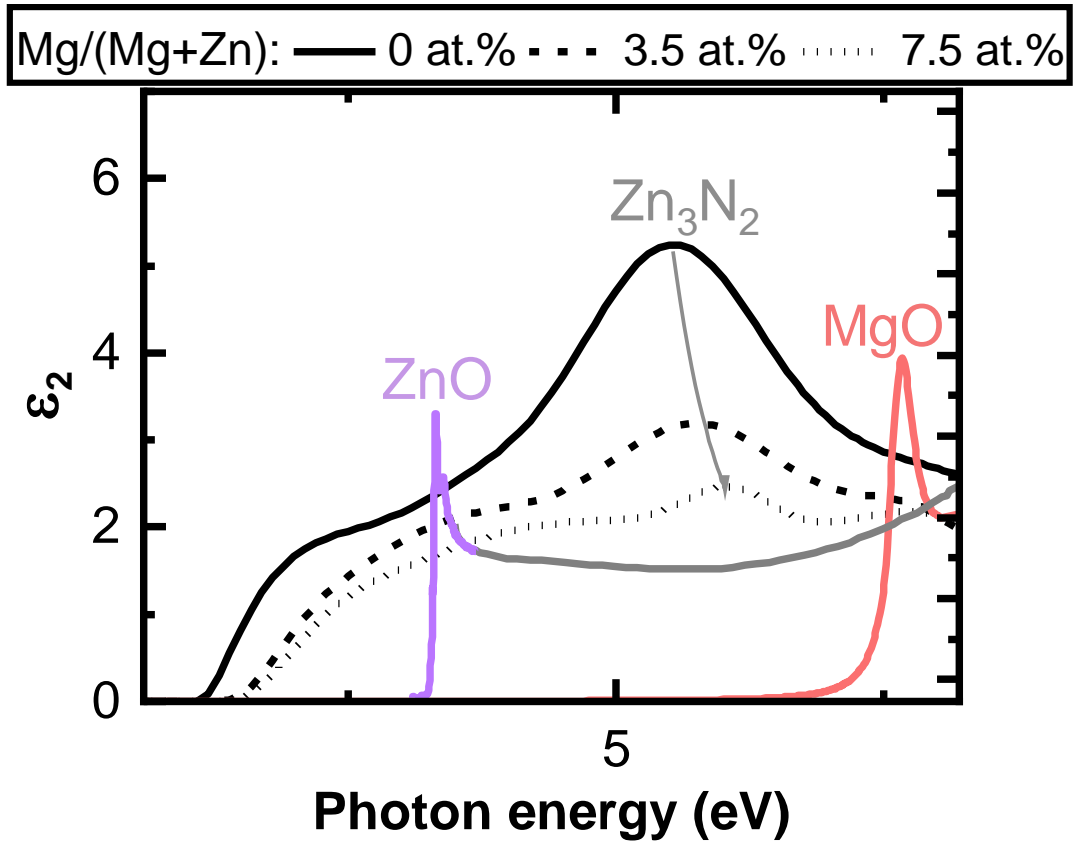
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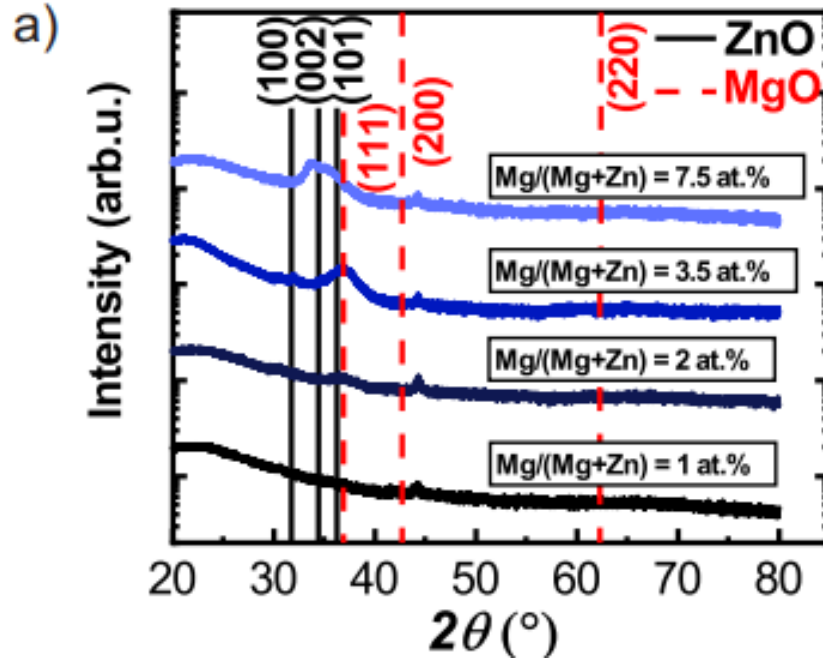
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OPTICAL PROPERTIES



STRUCTURAL PROPERTIES



MAGNETRON CO-SPUTTERING

- reactive in nitrogen and oxygen atmosphere
20sccm:1sccm

